

Study of the Growth of Magnesium Oxide Thin Films Using X-Ray Diffraction Technique: Mini Review

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Abstract

X-ray diffraction method has been used by many researchers in order to study the structure of films. In this work, amorphous structure or polycrystalline magnesium oxide thin films could be identified using this technique. Furthermore, the grain sizes could be measured using X-ray diffraction data as well.

Keywords: Magnesium oxide, Thin films, Semiconductor, Deposition, Grain size

Introduction

Oxide materials [1-12] and metal chalcogenide thin films [13-21] are widely employed in the producing of solar cells, sensor devices, laser devices, optoelectronics devices, integrated circuits, and microelectronics. There are many groups of scientists from different countries involved to study these materials [22-29].

In this work, magnesium oxide (MgO) films were prepared using various deposition techniques. Magnesium oxide was chosen due to it has a high melting temperature, stable at atmospheric and large yield of secondary electrons during the bombardment by ions. The obtained films will be investigated using X-ray diffraction technique.

Literature Survey

X-ray diffraction (XRD) technique is mostly employed in materials sciences for the measurement of compounds. Many scientists point out some advantages of XRD such as it gives qualitative and quantitative of crystalline compounds [30-36].

Metal organic chemical vapor deposition (MOCVD) method has been used to prepare MgO films as described by Boo et al. [37]. The XRD patterns confirm that the obtained films with high crystalline and a preferred (111) plane on both Si (100) and c-plane sapphire substrates. Similar growth texture was also detected when the films were synthesized using RF ion plating method as proposed by Kenichi et al. [38]. Manin et al. [39] produced MgO films using MOCVD method. The obtained experimental results support that the oxygen low rate and temperature of the substrate were considered to be the most critical in order to determine the structure of

samples. Dyachenko et al. [40] have reported that MgO films were deposited onto glass substrate using spray pyrolysis method under various substrate temperatures. The XRD data confirm that the quality of MgO film's textures increases with increasing the substrate temperature from 370 °C to 420 °C. In other case, (200) preferential orientation was observed for the films prepared at 800 °C using sol-gel method as concluded by Ho et al. [41]. Chemical vapor deposition method was used to prepare MgO films as reported by Toshiro et al. [42]. They found that highly (100) orientation can be seen in XRD patterns for the films prepared at a reaction temperature above 450 °C.

XRD technique has been used by Kurtaran et al. [43] in order to investigate the structure of sprayed MgO films. They claim that amorphous structure and polycrystalline nature could be seen for as-deposited films and annealed samples, respectively. On the other hand, Mahadeva et al. [44] discussed the XRD patterns for the MgO films prepared under various oxygen partial pressures in the working gas. They found that the films are mostly amorphous in the as-deposited conditions. However, the MgO peaks are more significantly appear in the films deposited in oxygen partial pressure of 10 % and annealed films.

The grain size could be determined using XRD data. MgO films were prepared using spray pyrolysis at various temperatures (425-525 °C). The grain size indicates a slight increase as the temperature increased as pointed out by Faraq et al. [45]. On the other hand, MgO films were synthesized using spray pyrolysis method by Nisatharaju et al. [46]. The average grain size was calculated and was in the order of nanometer (14nm).

Conclusion

X-ray diffraction analysis was employed as the characterization tool for optimizing the magnesium oxide films growth conditions. The crystalline structure, amorphous and grain size could be determined using this tool.

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Conflict of Interest

Author has declared that no competing interests exist.

References

1. Ismail RA, Ghafari S, Kadhim GA (2013) Preparation and characterization of nanostructure nickel oxide thin films by spray pyrolysis, *Applied Nanoscience* 3: 509-514.
2. Jlassi M, Sta I, Hajji M, Ezzaouia H (2014) Optical and electrical properties of nickel oxide thin films synthesized by sol-gel spin coating. *Mater Sci Semicond Processing* 21: 7-13.
3. Patil PS, Kadam LD (2002) *Applied Surface Science*. 199: 211-221.
4. Leng D, Wu L, Jiang H, Zhao Y, Zhang J, et al. (2012) Preparation and Properties of SnO₂ Film Deposited by Magnetron Sputtering. *Int J Photoenergy* 2012(2012): 6.
5. Stedile FC, Barros B ASD, Leite CVB, Freire FL., Baumvol, IJR, et al. (1989) Characterization of tin oxide thin films deposited by reactive sputtering *Thin Solid Films*, 170: 285-291.
6. Giulio MD, Manno D, Micocci G, Rella R, Siciliano P, et al. (1993) Growth and characterization of tin oxide thin films prepared by reactive sputtering. *Sol Energy Mater Sol Cells* 31(2): 235-242.
7. Desai SP, Suryawanshi MP, Bhosale SM, Kim JH, Moholkar AV, et al. (2015) Influence of growth temperature on the physic-chemical properties of sprayed cadmium oxide thin films. *Ceram Int* 41(3): 4867-4873.
8. Uplane MD, Kshirsagar PN, Lokhande BJ, Lokhande CD (1999) Preparation of cadmium oxide films by spray pyrolysis and its conversion into cadmium chalcogenide films. *Indian J Pure Appl Phys* 37: 616-619.
9. Lokhande BJ, Uplane MD (2001) Effect of deposition temperature on spray deposited cadmium oxide films. *Mater Res Bull* 36(3-4): 439-447.
10. Zhao ZW, Tay BK, Yu GQ, Chua DHC, Lau SP, et al. (2004) Optical properties of aluminium oxide thin films prepared by room temperature by off plane filtered cathodic vacuum arc system. *Thin Solid Films* 447-448(30): 14-19.
11. Zhao Z, Tay BK (2012) Property study of aluminium oxide thin films by thermal annealing. *Phys Status Solidi C* 9(1): 77-80.
12. Nursen A, Philippe FS, Johan L, Henk V, Dirk P, et al. (2011) Optical and structural properties of aluminium oxide thin films prepared by a non-aqueous sol gel technique. *J Sol Gel Sci Technol* 59(2): 327-333.
13. Sathishkumar R, Devakirubai E, David A, Tamilselvan S, Nithiyantham S, et al. (2017) Structural and optical studies of cadmium sulfide (CdS) thin film by chemical bath deposition (CBD). *Mater Focus* 6(1): 41-46.
14. Salh A, Moon K, Park H, Kim W (2017) Effect of different cadmium salts on the properties of chemical bath deposited CdS thin films and Cu(InGa)Se₂ solar cells. *Thin Solid Films* 625: 56-61.
15. Amira H, Hager M (2017) Growth of different phases and morphological features of MnS thin films by chemical bath deposition: Effect of deposition parameters and annealing. *J Solid State Chem* 247: 120-130.
16. Anuar K, Ho SM, Loh YY, Saravanan N (2010) Structural and morphological characterization of chemical bath deposition of FeS thin films in the presence of sodium tartrate as a complexing agent. *Silpakorn Univ Sci Technol J* 4(2): 36-42.
17. Ho SM, Saravanan N, Anuar K, Tan WT (2012) Temperature dependent surface topography analysis of SnSe thin films using atomic force microscopy. *Asian J Res Chem* 5(2): 291-294.
18. Daniel T, Henry J, Mohanraj K, Sivakumar G (2016) Fabrication of ITO/Ag₃SbS₃/CdX(X=S,Se) thin film heterojunctions for photo sensing applications. *Mater Res Express* p. 3.
19. Ho SM, Anuar K, Atan S, Saravanan N (2010) X-ray diffraction and atomic force microscopy studies of chemical bath deposited FeS thin films. *Stud Univ Babes-Bolyai Chem* 55(3): 5-11.
20. Mukherjee A, Ghosh P, Fu M, Aboud A, Mitra P, et al. (2016) Microstructural characterization of chemical bath deposition synthesized CdS thin films: Application as H₂S sensor. *Adv Sci Lett* 22(1): 179-183(5).
21. Ho SM, Anuar K, Nani R (2011) Atomic force microscopy studies of zinc sulfide thin films. *Int J Adv Eng Sci Technol* 7(1): 169-172.
22. Fernandes PA, Salome PMP, Cunha AF (2010) A study of ternary Cu₂SnS₃ and Cu₃SnS₄ thin films prepared by sulfurizing stacked metal precursors. *J Phys D: Appl Phys* 43(21): 215403.
23. Ham S, Jeon S, Lee U, Paeng K, Myung N, et al. (2008) Photo electrochemical deposition of CdZnSe thin films on the Se-modified Au electrode. *Bull Korean Chem Soc* 29: 939-942.
24. Isi PO, Ekwo PI (2013) Growth and characterization of lead selenide thin films by chemical bath deposition. *Res J Eng Sci* 2(8): 15-19.
25. Khomane AS (2012) Synthesis and characterization of chemically deposited Cu₂-xSe thin films. *Arch Appl Sci Res* 4(4): 1857-1863.
26. Mahmoud FA, Sayed MH (2011) Preparation and characterization of sprayed AgInSe₂ thin films. *Chalcogenide Lett* 8(10): 595-600.
27. Mishack NN, Chinedu EE (2010) Synthesis and characterization of chemical bath deposited CdCoS thin film. *Chalcogenide Lett* 7(1): 31-38.
28. Murali KR, Balasubramanian M (2010) Characteristics of pulse plated CdxZn1-xSe films. *Curr Appl Phys* 10(3): 734-739.
29. Osuwa JC, Oriaku CI, Atuloma CM (2010) Study of physical properties of ternary Cu₁₁Cd₄₀S₄₉. *Chalcogenide Lett* 7(6): 383-388.
30. Anuar K, Ho SM, Tan WT, Atan S, Saravanan N, et al. (2011) Chemical bath deposition of ZnSe thin films: SEM and XRD. *Eur J Appl Sci* 3(3): 113-116.
31. Vanita SR, Chandrakant DL, Vilas VK (2017) Photo electrochemical studies on electrodeposited indium doped CdSe thin films using aqueous bath. *J Electroanal Chem* 788: 137-143.
32. Saravanan N, Anuar K, Ho SM, Tan WT, Dzulkefly K, et al. (2010) Preparation and characterization of PbSe thin films by chemical bath deposition. *Jurnal Kimia* 4: 1-6.
33. Ersin Y, Yasin Y (2017) Fabrication and characterization of Sr-doped PbS thin films grown by CBD. *Ceram Int* 43(1): 407-413.
34. Anuar K, Tan WT, Ho SM (2013) Thickness dependent characteristics of chemically deposited tin sulfide films. *Universal J Chem* 1(4): 170-174.
35. Baligh T, Abdelaziz G, Illia D, Marta MN, Alberto V, et al. (2016) Engineering of electronic and optical properties of PbS thin films via Cu doping. *SuperlatticesMicrostruct* 97: 519-528.

36. Anuar K, Tan WT, Ho SM, Jelas HM, Saravanan N, et al. (2007) Cyclic voltammetry study of copper tin sulfide compounds. *Pacific J Sci Technol* 8(2): 252-260.
37. Boo J, Lee S, Yu K, Koh W, Kim Y, et al. (1999) Growth of magnesium oxide thin films using single molecular precursors by metal-organic chemical vapor deposition. *Thin Solid Films* 341(1-2): 63-67.
38. Kenichi O, Hiroyuki M, Kunihiro K, Yoichi M (2003) MgO thin films for plasma display panel formed by plasma process. *Surf Coat Technol* 169-170: 562-565.
39. Manin M, Thollon S, Emieux F, Berthome G, Pons M, et al. (2005) Deposition of MgO thin film by liquid pulsed injection MOCVD. *Surf Coat Technol* 200(5-6): 1424-1429.
40. Dyachenko AV, Opanasuyk AS, Kurbatov DI, Bolshanina SB, Kuznetsov VM, et al. (2014) Structural properties of magnesium oxide thin films deposited by spray pyrolysis technique. *Proc Int Conf Nanomater: Appl Properties* 3(1): 01PCSI05(4pp).
41. Ho I, Xu Y, Mackenzie JD (1997) Electrical and optical properties of MgO thin film prepared by sol-gel technique. *J Sol Gel Sci Technol* 9(3): 295-301.
42. Toshiro M, Jun S (1990) Magnesium oxide thin films prepared by chemical vapor deposition from magnesium 2-ethylhexanoate. *Japanese J Appl Phys* 29(5).
43. Kurtaran S, Akyuz I, Atay F (2013) Evaluation of optical parameters and characterization of ultrasonically sprayed MgO films by spectroscopic ellipsometry. *Appl Surf Sci* 265: 709-713.
44. Mahadeva SK, Fan J, Biswas A, Sreelatha KS, Belova L, et al. (2013) Magnetism of amorphous and nano-crystallized Dc-sputter deposited MgO thin films. *Nanomater* 3(3): 486-497.
45. Faraq MA, Okr M, Mahani RM, Turkey GM, Afify HH, et al. (2014) Investigation of dielectric and optical properties of MgO thin films. *Int J Adv Eng Technol Comput Sci* 1(1): 1-9.
46. Nisatharaju S, Ayyappa R, Balamurugan D (2014) Structural, morphological and optical characterization of spray deposited MgO thin film. *Asian J Appl Sci* 7(8): 780-785.



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